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**PATENT**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Application No.: **10/549,609**

Filing Date: September 20, 2005

Applicant: Tomoko AKAI et al.

Conf. No.: 8155

Group Art Unit: 1791

Examiner: Margaret Squalls

Title: METHOD FOR PRODUCING HIGH SILICATE GLASS  
AND HIGH SILICATE GLASS (as amended)

Atty. Dkt. No.: 12480-000144/US

Customer Service Window  
Randolph Building  
401 Dulany Street  
Alexandria, VA 22314  
Mail Stop **Amendment**

June 10, 2010

**AMENDMENT UNDER 37 C.F.R. § 1.111**

Dear Sir:

In response to the Office Action (hereinafter 'Action') mailed on March 11, 2010, the following amendments and remarks are respectfully submitted in connection with the above-identified patent application.

	Claims remaining after Amendment		Highest number previously paid for		Present extra
<b>Total</b>	18	-	20	=	0
<b>Independent</b>	1	-	3	=	0